

What is claimed:

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1. A method for providing a raised feature on a surface of a prototype model characterized by the steps of:
- 5 (a) providing a model having at least one surface on which to provide a raised feature;
- (b) coating the surface with a photo resist to a predetermined thickness;
- (c) providing means for preventing exposure of a first portion of the photo resist to a radiation source while allowing exposure of a second portion of the photo resist wherein the second portion of the photo resist provides the raised feature;
- 10 (d) exposing the surface to a radiation source to chemically alter the second portions of the photo resist; and,
- (e) removing the first portion of the photo resist from the surface while leaving the raised feature formed by the exposed photo resist on the surface.
- 15 2. The method of claim 1 wherein the step of coating the surface with a photo resist is further characterized by the steps of applying the photo resist in more than one layer.
- 20 3. The method of claim 2 further characterized by the step of:
- allowing sufficient drying time between successive layers of the photo resist.
4. The method of claim 1 further characterized by the step of:
- 25 cleaning the surface of the prototype model before the step of coating the surface with the photo resist.
5. The method of claim 1 further characterized by the steps of:
- inspecting the raised feature after the step of removing the first portion
- 30 of the photo resist; and,
- repeating steps (b) - (e) to enhance the raised feature.

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6. The method of claim 1 wherein the step of providing a model is characterized by: ~~A~~

providing a model formed by a stereolithography process.

- 5 7. A prototype model having a raised feature on at least one surface wherein the raised feature is formed by the method of claim 1.

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